

Patent Assignment Abstract of Title

Total Assignments: 1

Application #: 10043190 **Filing Dt:** 01/14/2002 **Patent #:** NONE **Issue Dt:**
PCT #: NONE **Publication #:** 20020096188 **Pub Dt:** 07/25/2001

Inventor: Hiroshi Nogami

Title: Method of cleaning CVD device

Assignment: 1

Reel/Frame: 012473/0209 **Received:** 01/22/2002 **Recorded:** 01/14/2002 **Mailed:** 03/13/2002 **Pages:**

Conveyance: ASSIGNMENT OF ASSIGNORS INTEREST (SEE DOCUMENT FOR DETAILS).

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Exec Dt: 01/11/2002

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Search Results as of: 6/13/2003 1:55:32 P.M.

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 Web interface last modified: Oct. 5, 2002

WEST Search History

DATE: Friday, June 13, 2003

<u>Set Name</u>	<u>Query</u>	<u>Hit Count</u>	<u>Set Name</u>
side by side			result set
<i>DB=USPT,PGPB,JPAB,EPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>			
L9	L6 and (He or Ar or Ne or Kr or Xe)	63	L9
L8	L6 same (He or Ar or Ne or Kr or Xe)	6	L8
L7	L6 and l5	62	L7
L6	(CVD or chamber or vessel) same clean\$3 same (oxygen with fluor\$3) ((134/1.1 134/21 134/22.1)!.CCLS. (216/63 216/64 216/67 L5)!.CCLS. (204/298.01)!.CCLS. (438/905)!.CCLS. (156/345.29 156/345.35 156/345.47)!.CCLS.)	206	L6
		5149	L5
<i>DB=JPAB,EPAB,DWPI; PLUR=YES; OP=ADJ</i>			
L4	L1 and chemical vapor deposition	0	L4
L3	L1 and clean\$3	5	L3
L2	L1 and CVD	0	L2
L1	nogami-hiroshi\$.in.	108	L1

END OF SEARCH HISTORY